Application No. 10/666,252 Amendment dated April 9, 2007

After Final Office Action of November 7, 2006

AMENDMENTS TO THE CLAIMS

1. (Currently Amended) A liquid organometallic compound vaporizing and feeding

system comprising:

(1) a liquid reagent container containing a liquid reagent containing a liquid

organometallic compound and impurities, a vaporizer for vaporizing the liquid reagent

organometablic-commound, a liquid reagent passageway connecting said container to said

vaporizer and having a liquid mass flow controller disposed therein for controlling the flow rate

of the liquid reasent oreanometallic compound([.1];

(2) a carrier gas source, a carrier gas passageway connecting said carrier gas source to

said vaporizer so as to carry a mixture of vaporized liquid reagent and the carrier gas and having

a gas mass flow controller disposed therein for controlling the flow rate of the carrier gas[[,]];

(3) a sample gas passageway including one end connected to a gas outlet of said

vaporizer and another end eonnected connectable to a sample inlet of an ICP emission

spectrometer, and having an in-line monitor for measuring concentration of vaporized liquid

reagent in the mixture disposed therein[[,]]; and

(4) a gas cylinder filled with a standard gas for calibration, and a standard gas

passageway connecting said gas cylinder to said sample gas passageway at a position

downstream of said in-line monitor and having a gas mass flow controller disposed therein for

controlling the flow rate of the standard gas.

2. (Currently Amended) The vaporizing and feeding system of claim 1, comprising;

a plurality of calibration standard gas cylinders[[,]]; and

2

GMM/TK/enm

Decket No.: 0171-1016P

Application No. 10/666,252 Docket No.: 0171-1016P Amendment dated April 9, 2007

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a corresponding plurality of standard gas passageways each having a gas mass flow

controller disposed therein for controlling the flow rate of the corresponding standard gas.

3. (New) The vaporizing and feeding system of claim 1, wherein the in-line monitor

comprises:

an IR absorption cell, through which the organometallic compound gas is passed; and

an IR detector for measuring an IR absorption characteristic of the gas organometallic

3

compound gas.

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